

U.S. Department of Commerce, Patent and Trademark Office (PTO Form 1449 modified)		Docket No AMAT/6437/ETCH/METAL/JB1	Serial No. 10/092,456
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Applicant Hwang, et al.	Confirmation No. 1212
(Use several sheets if necessary)		Filing Date March 6, 2002	Group 2818
	Examiner Dung Anh Le		

U.S. Patent Documents

*Examiner Initial	Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
A1						
A2						
A3						
A4						
A5						

Foreign Patent Documents

*Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation	
						YES	NO
B1						<input type="checkbox"/>	<input type="checkbox"/>
B2						<input type="checkbox"/>	<input type="checkbox"/>
B3						<input type="checkbox"/>	<input type="checkbox"/>
B4						<input type="checkbox"/>	<input type="checkbox"/>
B5						<input type="checkbox"/>	<input type="checkbox"/>

OTHER ART

*Examiner Initial	Including Author, Title, Date, Pertinent Pages, Etc.		
<i>Dle</i>	C1	Jung, K.B., et al., "Long term stability of dry etched magnetoresistive random access memory elements", <i>Journal of Vacuum Science and Technology Part A</i> ; American Institute of Physics, New York, U.S., Vol. 18, No. 1, January 2000 (2000-01), pp. 268-272, XP001145970, ISSN: 0734-2101.	
<i>Dle</i>	C2	van Delft, F.C.M.J.M., et al., "The etch mechanisms of magnetic materials in an HCl plasma", <i>Fusion Technology and Plasmas Session of the Twelfth International Vacuum Congress (IVC-12) and Eighth International Conference on Solid Surfaces (ICSS-8)</i> , The Hague, Netherlands, 12-16 Oct 1992, Vol. 200, No. 3, pp. 366-370, XP008022404, <i>Journal of Nuclear Materials</i> , May 1993, Netherlands, ISSN: 0022-3115.	
<i>Dle</i>	C3	Cho, H. et al., "Inductively coupled plasma etching of CoFeB, CoZr, CoSm and FeMn thin films in interhalogen mixtures", <i>Materials Science and Engineering B (Solid-State Materials for Advanced Technology)</i> , 15 June 1999, Elsevier, Switzerland, Vol. B60, No. 2, pp. 107-111, XP004175032, ISSN: 0921-5107.	

Examiner

Dle

Date Considered

Apr. 1 - 2004

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.